



00839.000449

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

ATSUSHI KOIKE ET AL.

Application No.: 09/982,846

Filed: October 22, 2001

For: METHOD FOR FORMING
A DEPOSITED FILM BY
PLASMA CHEMICAL VAPOR
DEPOSITION

Examiner: E. Kielin

Group Art Unit: 2813

October 21, 2002

Commissioner for Patents
Washington, D.C. 20231

AMENDMENT AND RESPONSE TO RESTRICTION REQUIREMENT

Sir:

In response to the Office Action dated September 20, 2002, Applicants respectfully request entry of the following amendments and comments into the file of the above-identified application.

I hereby certify that this correspondence is being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231 on

October 21, 2002

(Date of Deposit)

Alan P. Force

(Name of Attorney for Applicant)

Alan P. Force

Signature

October 21, 2002

Date of Signature

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